



## Substitue for form 1449A/PTO **INFORMATION DISCLOSURE** STATEMENT BY APPLICANT

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Sheet 1 of 2



Complete if Known	
Application Number	09/945507
Filing Date	August 30, 2001
First Named Inventor	Forbes, Leonard
Group Art Unit	2818
Examiner Name	Unknown

Attorney Docket No: 01303.014US1

- ,		US F	PATENT DOCUM	ENTS	
Examiner Initials *	Cite No <sup>1</sup>	USP Document No	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures appear
		US-4412902	11/01/1983	Michikami, Osamu, et al	
51)		US-4780424	10/25/1988	Holler, Mark A	
1		US-5350738	09/27/1994	Hase, Takashi, et al	
		US-5691230	11/25/1997	Forbes, L.	
		US-5801401	09/01/1998	Forbes, L.	
		US-5852306	12/22/1998	Forbes, Leonard	
40		US-5936274	08/10/1999	Forbes, L., et al	
1		US-5981350	11/09/1999	Geusic, J. E., et al	
		US-6025627	02/15/2000	Forbes, L., et al	
		US-6031263	02/29/2000	Forbes, L., et al	
		US-6134175	10/17/2000	Forbes, L., et al	
		US-6143636	11/07/2000	Forbes, L., et al	
51)		US-6208164	03/27/2001	Noble, W. P., et al	

		FOREI	GN PATENT DOC	CUMENTS		
Examiner Initials*	Cite No <sup>1</sup>	Foreign Document No	Publication Date	Name of Patentee or Applicant ofcited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures appear	T 2

•	OTHE	ER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item(book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²
S		ARYA, S., "Conduction Properties of Thin Al <sub>2</sub> O <sub>3</sub> Films", <u>Thin Solid Films</u> , <u>91</u> , (1982), pp. 363-374	
থ)		DIPERT, BRIAN., "Flash Memory Goes Mainstream", <u>IEEE Spectrum, 30,</u> (October 1993),48-52	
S	<del></del>	ELDRIDGE, J.M., "Growth of Thin PbO Layers on Lead Films", Surface Science, Vol. 40, (1973),512-530	
<n)< td=""><td></td><td>ELDRIDGE, J., "Measurement of Tunnel Current Density in a Metal-Oxide-Metal System as a Function of Oxide Thickness", Proc. 12th Intern. Conf. on Low Temperature Physics, (1971),pp. 427-428</td><td></td></n)<>		ELDRIDGE, J., "Measurement of Tunnel Current Density in a Metal-Oxide-Metal System as a Function of Oxide Thickness", Proc. 12th Intern. Conf. on Low Temperature Physics, (1971),pp. 427-428	
(V)		GREINER, J.G., "Josephson Tunneling Barriers by rf Sputter Etching in an Oxygen Plasma", <u>Journal of Applied Physics, vol. 42, no. 12,</u> (November 1971),5151-5155	
CP CP		GREINER, J., "Oxidation of lead films by rf sputter etching in an oxygen plasma", Journal of Applied Physics, 45(1), (1974),pp . 32-37	
S		GUNDLACH, K., "Logarithmic Conductivity of Al-Al <sub>2</sub> O <sub>3</sub> -Al Tunneling Junctions Produced by Plasma and by Thermal Oxidation", Surface Science, 27, (1971),	

EXAMINER	SON DINH	DATE CONSIDERED	[/11/0]	3
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<b>(1)</b>		pp. 125-141	
S		HURYCH, Z. "Influence of Non-Uniform Thickness of Dielectric Layers on Capacitance and Tunnel Currents", Solid-State Electronics, vol. 9, (1966),967-979	
)		KUBASCHEWSKI, O. "Oxidation of Metals and Alloys", <u>Butterworths. London</u> , (1962),53-63	
		LUAN, H.F., "High Quality Ta <sub>2</sub> O <sub>5</sub> Gate Dielectrics with T <sub>ox,eq</sub> <10À", <u>IEDM</u> <u>Technical Digest</u> , (1999),141-143	
		MASUOKA, FUJIO.,"A 256K flash EEPROM using Triple Polysilicon Technology", 1985 IEEE International Solid-State Circuits Conference. Digest of Technical Papers, (02/1985),168-169	:
		MASUOKA, FUJIO., "A new Flash E <sup>2</sup> PROM Cell using Triple Polysilicon Technology", International Electron Devices Meeting. Technical Digest, (12/1984),464-467	
		MORI, S., "Reliable CVD Inter-Poly Dielectrics for Advanced E&EEPROM", 1985 Symposium on VSLI Technology. Digest of Technical Papers, (1985), 16-17	
		PASHLEY, RICHARD D., "Flash Memories: the best of two worlds", IEEE Spectrum, (December/1989),30-33	
		POLLACK, S., "Tunneling Through Gaseous Oxidized Films of Al <sub>2</sub> O <sub>3</sub> ", Transactions of the Metallurgical Society of AIME, 233, (1965),pp. 497-501	
		ROBERTSON, J., "Schottky Barrier height of Tantalum oxide, barium strontium titanate, lead titanate, and strontium bismuth tantalate", <u>Applied Physics Letters</u> , vol. 74, no. 8, (02/22/1999),1168-1170	
		SHI, Y., "Tunneling Leakage Current in Ultrathin (<4 nm) Nitride/Oxide Stack Dielectrics", IEEE Electron Device Letters, 19(10), (October 1998),pp. 388-390	
59)		SIMMONS, J., "Generalized Formula for the Electric Tunnel Effect between Similar Electrodes Separated by a Thin Insulating Film", Journal of Applied Physics, 34(6), (1963),pp. 1793-1803	
(1)		SZE, S., Physics of Semiconductor Devices, Second Edition, (1981),pp. 553-556	

6/11/03 DATE CONSIDERED